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(12) **United States Design Patent** (10) **Patent No.:** **US D971,167 S**  
**Babu et al.** (45) **Date of Patent:** **\*\* Nov. 29, 2022**

(54) **LOWER SHIELD FOR A SUBSTRATE PROCESSING CHAMBER**

FOREIGN PATENT DOCUMENTS

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(\*\*) Term: **15 Years**

(21) Appl. No.: **29/778,108**

(57) **CLAIM**

(22) Filed: **Apr. 10, 2021**

The ornamental design for a lower shield for a substrate processing chamber, as shown and described.

**Related U.S. Application Data**

(62) Division of application No. 29/703,658, filed on Aug. 28, 2019, now Pat. No. Des. 931,241.

(51) **LOC (13) Cl.** ..... **13-03**

(52) **U.S. Cl.**  
USPC ..... **D13/182**

(58) **Field of Classification Search**  
USPC ..... D9/500, 516, 519, 535, 544, 738, 741;  
D24/108, 207, 210, 216, 222, 224, 229,  
D24/231, 232; D26/9, 11, 93, 104, 105,  
D26/110, 113, 114, 117; D15/150;  
(Continued)

**DESCRIPTION**

FIG. 1 is a top isometric view of a lower shield for a substrate processing chamber, according to the novel design. FIG. 2 is a top plan view thereof. FIG. 3 is a bottom plan view thereof. FIG. 4 is a front elevation view thereof. FIG. 5 is a back elevation view thereof. FIG. 6 is a right side elevation view thereof. FIG. 7 is a left side elevation view thereof; and, FIG. 8 is a cross-sectional view taken along line 8-8 in FIG. 2.

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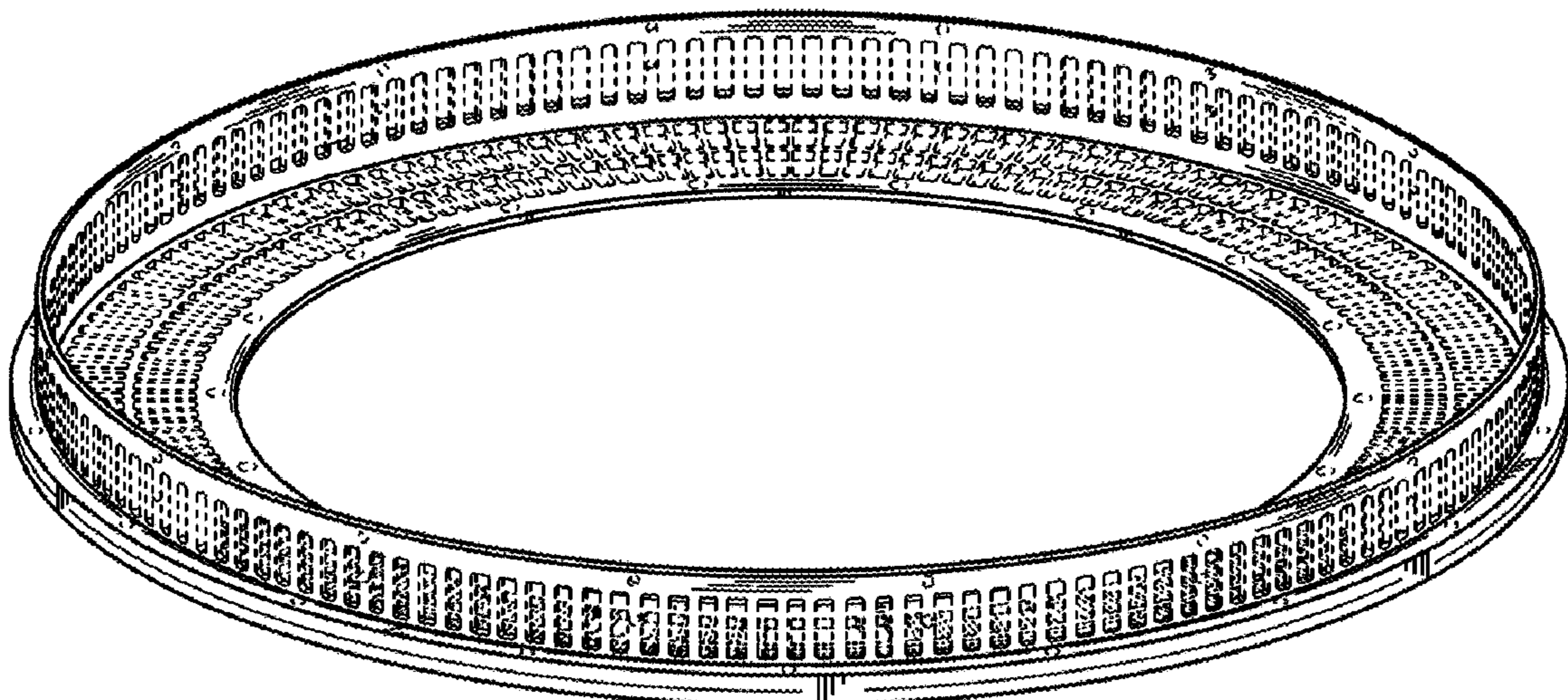
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The broken lines show portions of a lower shield for a substrate processing chamber that form no part of the claimed design.

(Continued)

**1 Claim, 5 Drawing Sheets**







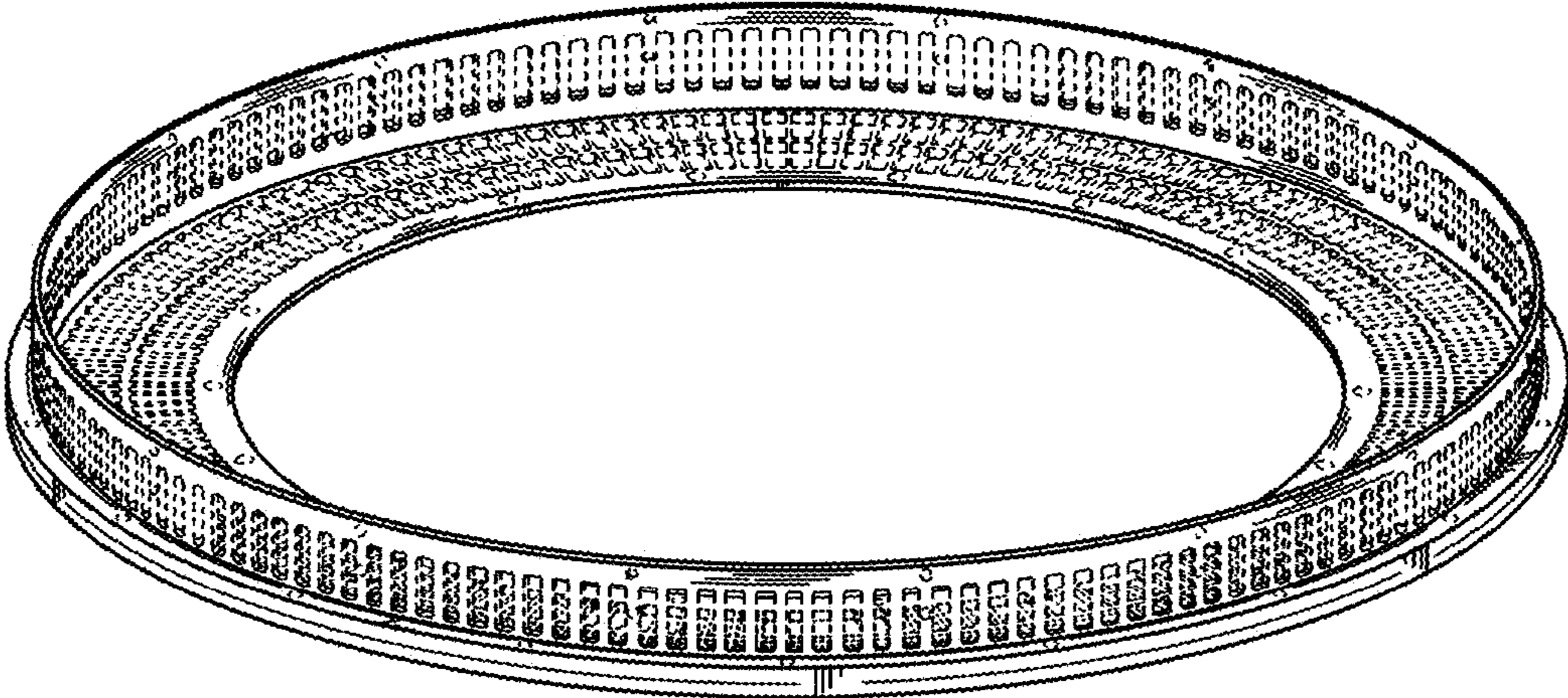


FIG. 1

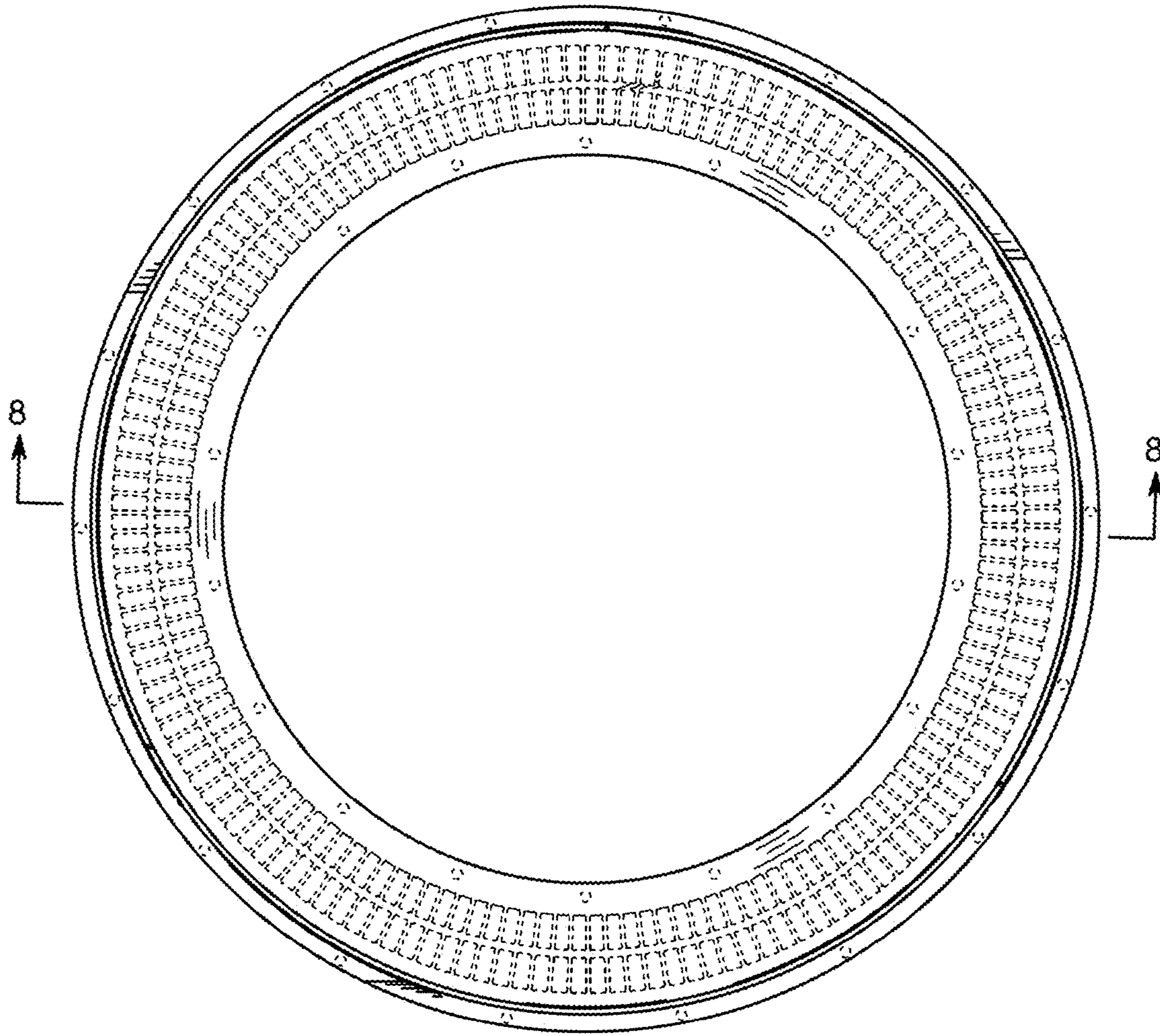


FIG. 2







FIG. 4



FIG. 5

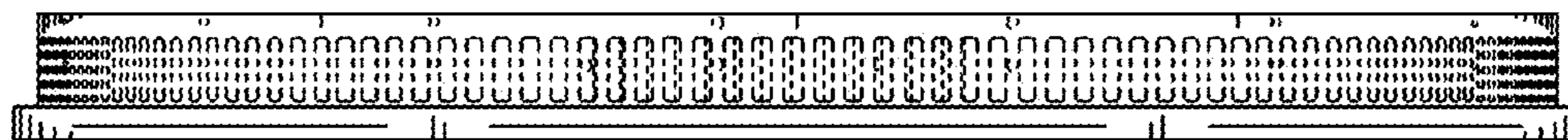


FIG. 6



FIG. 7



FIG. 8